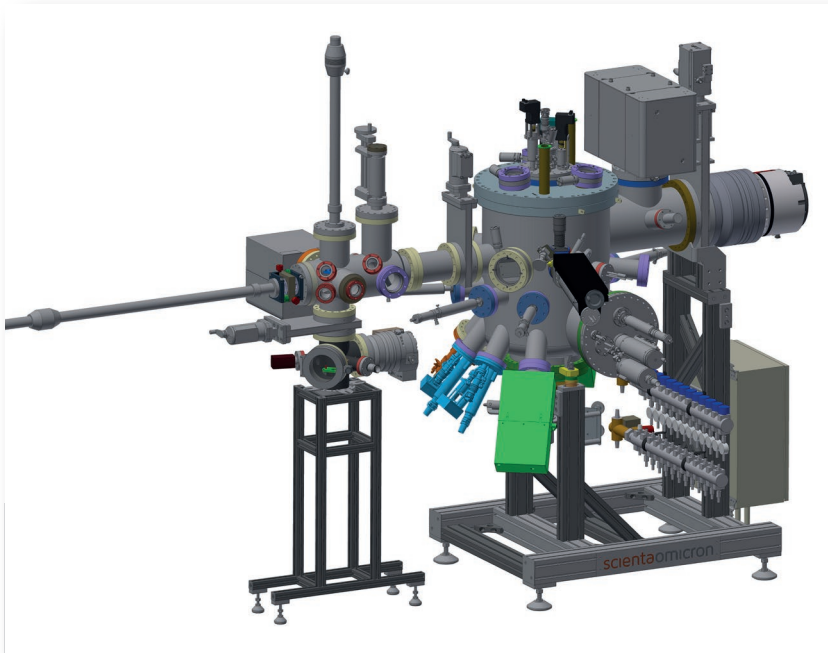


PVD 50 SYSTEM

UHV PVD Solution



PVD 50 System at a glance:

- PVD system for wafers up to 2" and surface science samples
- Compact footprint
- True UHV base pressure
- In-situ flux monitoring
- Growth process controlled by advanced software

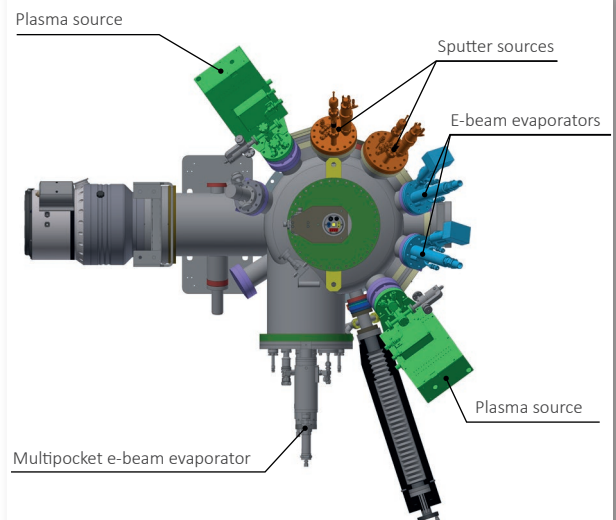
Versatile configuration options of the PVD 50 system enable high-quality thin film deposition of different material classes, like metals, oxides, magnetic materials and superconductor material systems.

The PVD 50 system is designed to fulfil the highest and most stringent requirements of modern thin-film deposition. Real Ultra High Vacuum (UHV) base pressure reduces contaminations in the grown films and enables integration to surface science analysis instruments. The PVD 50 is suitable and optimized for the growth of metals, oxides, magnetic materials and superconductor material systems.

Due to the small footprint the PVD 50 can be configured to be either a standalone system with

a buffer chamber and sample load lock or integrated with a linear transfer line or a radial distribution chamber.

All PVD 50 systems come with the MISTRAL control system together with a powerful evaporation control software. The control system is based on certified standard components for supreme reliability and provides a graphical status overview of all sensor values. With this software bundle, experiments can be conducted under well-controlled and reproducible conditions.



PVD 50 Source configuration consists of:

- 2x DN100CF Sputter sources
- 1x DN250CF Multi-Pocket electron beam evaporator
- 2x DN63CF Vertical e-beam evaporators
- 2x DN63CF Plasma sources

How to contact us:

America



Europe & Africa



Asia & Australia

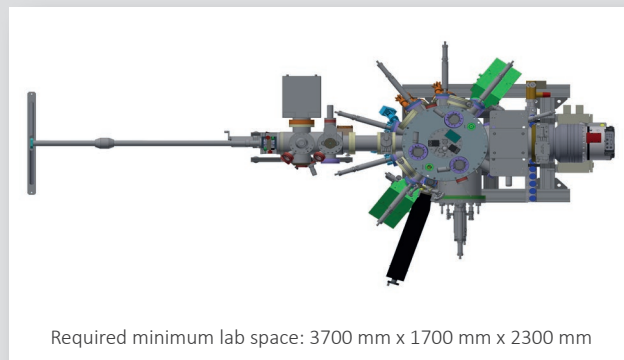


We have agents and sales representatives around the world- and right next door. Please check our website for your local contact and partner. Many thanks.
www.scientaomicron.com

Technical Data

Property	Target Specification*
Vacuum tank:	Stainless steel
Pressure:	$< 3 \times 10^{-10}$ mbar
Pressure sensor:	Ion gauge
Substrate size:	Up to 2" diameter
Sources:	2x DN100CF Sputter sources 1x DN250CF Multi-Pocket electron beam evaporator 2x DN63CF Vertical e-beam evaporators 2x DN63CF Plasma sources
Pumps:	1. Ion getter pump (IGP) and Cryopump 2. Ion getter pump (IGP) and Turbopump 3. Others available on request
Viewports:	Equipped with Viewport Shutters
Software package:	Growth control software included
Preconfig. flanges:	2x Quartz Micro Balance Quadrupole mass analyser (RGA) Pyrometer

* Specifications for standard configuration. Customizations can influence specifications. Please contact us for details.



Required minimum lab space: 3700 mm x 1700 mm x 2300 mm

How to contact us:

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